



INTERNATIONAL ATOMIC ENERGY AGENCY
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WINTER COLLEGE ON LASERS, ATOMIC AND MOLECULAR PHYSICS
(21 January - 22 March 1985)

SMR/115 - 34

SEMICONDUCTOR LASERS

2

PICOSECOND OPTOELECTRONICS

E.O. GÖBEL

PART I: SEMICONDUCTOR LASERS

PART II: OPTICAL PROPERTIES

PART III: PS-OPTOELECTRONICS

SEMICONDUCTOR LASERS & PICOSECOND OPTOELECTRONICS

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These are preliminary lecture notes, intended only for distribution to participants.
Missing or extra copies are available from Room 229.

SEMICONDUCTOR LASERS

2.

FUNDAMENTALS

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PART I

FUNDAMENTALS

EXCITATION (HETERO DIODE)

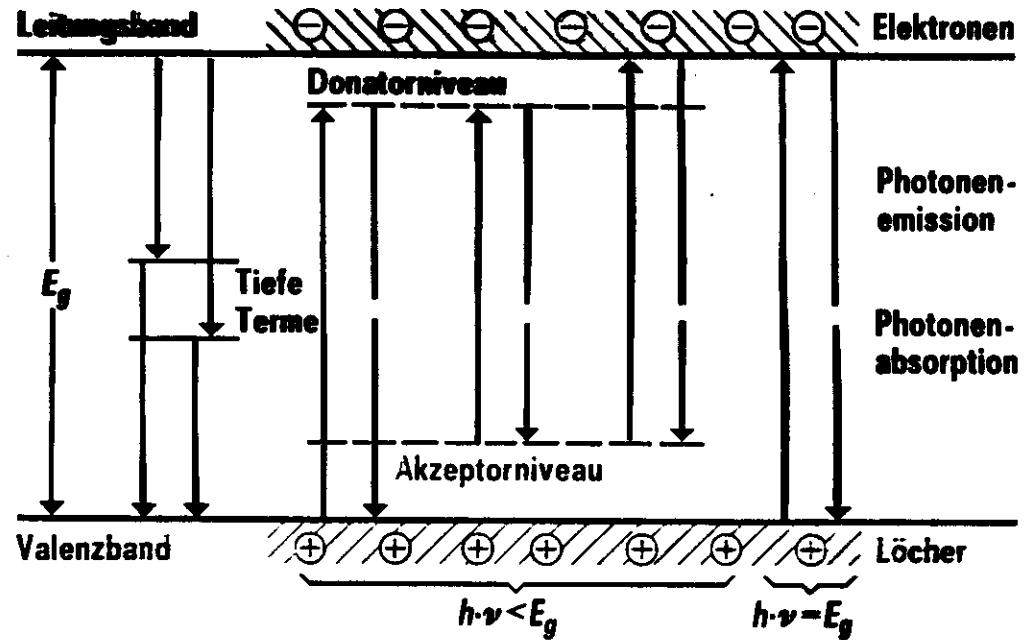
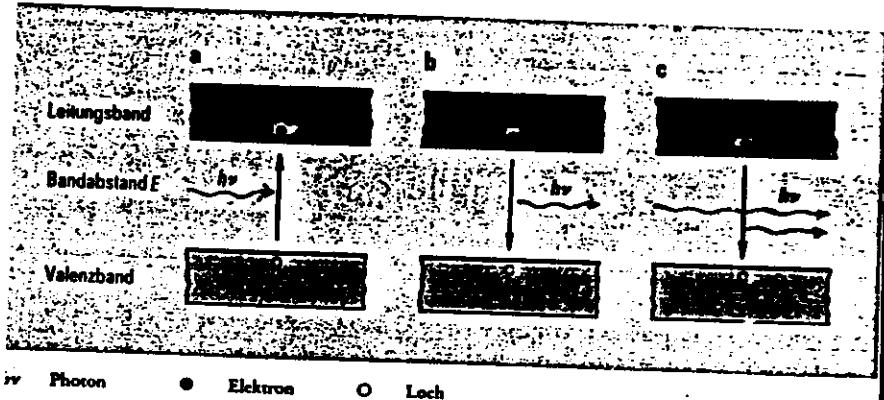
LASER STRUCTURE

QUANTUM WELL LASER

TECHNOLOGY

APPLICATIONS

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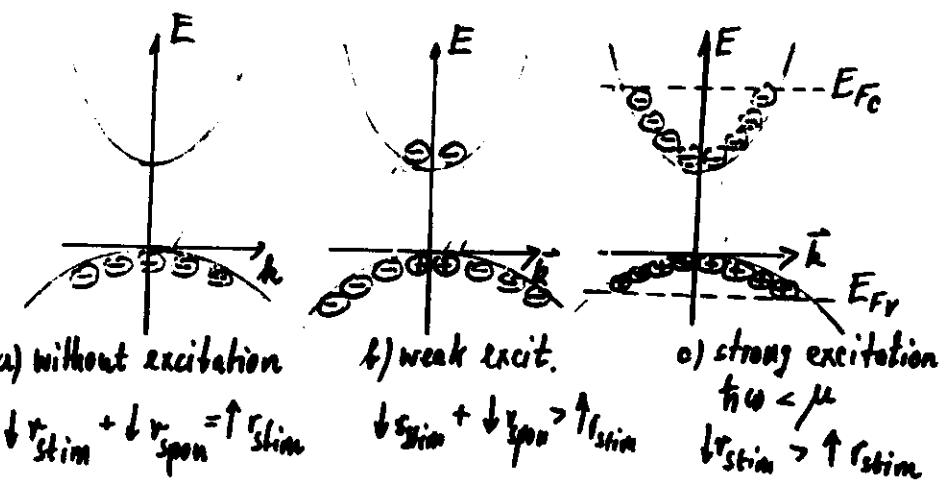
$$\text{Grenzwellenlänge } \lambda_{\text{grenz}} = \frac{h \cdot c}{E_g} \approx \frac{1240}{E_g \text{ (eV)}} \text{ (nm)}$$

Halbleiter	E_g (300 K)	λ_{grenz}	Bandübergang
Ge	0.7 eV	1800 nm	indirekt
Si	1.1 eV	1100 nm	indirekt
GaAs	1.4 eV	840 nm	direkt
GaP	2.3 eV	560 nm	indirekt
SiC	2.8 eV	440 nm	indirekt
GaN	3.5 eV	350 nm	direkt

h Planck'sches
Wirkungsquantum
 ν Frequenz ($\nu = \frac{c}{\lambda}$)
 c Lichtgeschwindigkeit
 E_g Energielücke

Bänderschema im Ortsraum und Grenzwellenlängen

Band - to - Band Optical Transitions

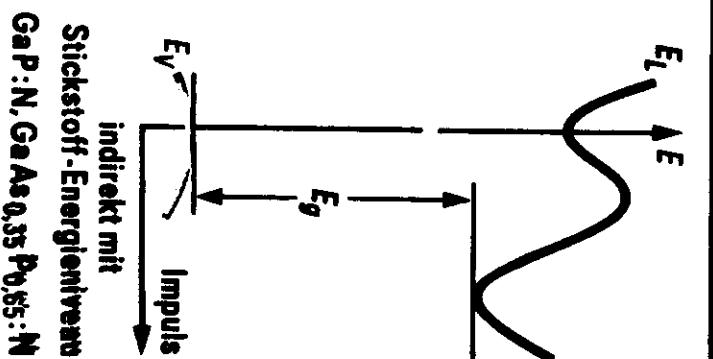
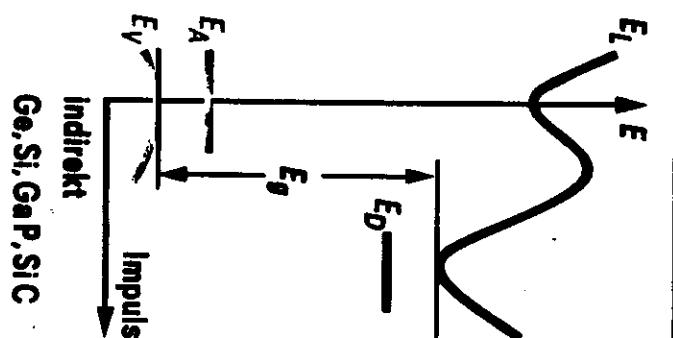
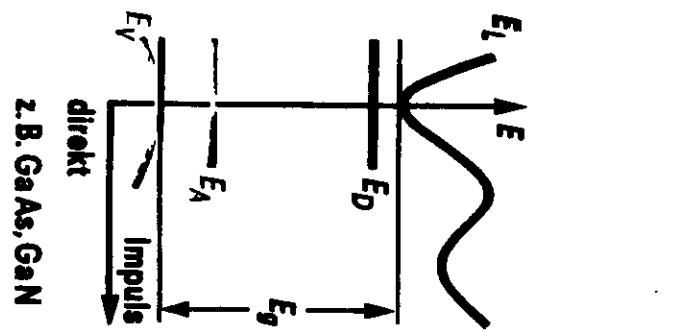


$$f_c(E'_c) = \frac{1}{e^{(E'_c - E_{Fc})/kT} + 1}$$

$$f_v(E'_v) = \frac{1}{e^{(E'_v - E_{Fv})/kT} + 1}$$

Transition between E'_c and E'_v : $E'_c - E'_v = \hbar\omega$

$$1.) \quad r'_{spont} \downarrow : \quad r'_{spont}(\hbar\omega) = C_{cv} \cdot f_c(E'_c) [1 - f_v(E'_v)]$$



E_L Energieniveau Leitungsband
 E_V Energieniveau Valenzband
 E_N Energieniveau der Stickstoffdotierung

E_D Donatoren-Energieniveau
 E_A Akzeptoren-Energieniveau

Ge, Si, GaP, SiC

GaN, GeAs 0,35 P 0,65 : N

Bänderschema im Impultraum

BR01572

$$2) r_{\text{stim}} \downarrow : r_{\text{stim}}(\hbar\omega) = B_{cv} f_c (1-f_v) \cdot \tilde{N}$$

$$3) r_{\text{stim}} \uparrow : r_{\text{stim}}(\hbar\omega) = B_{vc} f_v (1-f_c) \cdot \tilde{N}$$

detailed balance (without excitation):

$$r'_{\text{spont}} + \tilde{N}_0 \cdot r_{\text{stim}} \downarrow = \tilde{N}_0 \cdot r_{\text{stim}} \uparrow$$

$$\Rightarrow C_{cv} = B_{cv} = B_{vc} \equiv B(\hbar\omega)$$

$$r'_{\text{stim}}(\hbar\omega) = r_{\text{stim}}(\hbar\omega) \downarrow - r_{\text{stim}}(\hbar\omega) \uparrow = \\ r'_{\text{spont}}(\hbar\omega) \left\{ 1 - e^{(\hbar\omega - (E_{Fc} - E_{Fv})) / kT} \right\}$$

$$r'_{\text{stim}}(\hbar\omega) > 0 \Leftrightarrow \hbar\omega < \Delta E_F$$

$$\left(\frac{1}{2} N_e > \frac{g_2 \cdot N_g}{g_1} \right)$$

total rate:

$$r_{\text{spont}}(\hbar\omega) = \sum_{\substack{E'_c \\ E'_c - \hbar\omega = E_v}} r'_{\text{spont}}(\hbar\omega)$$

two cases:

1.) only transitions with $\vec{k}_c - \vec{k}_v = \vec{k}_{ph} \approx 0$
(k -selection rule)

$$r_{\text{spont}}(\hbar\omega) = B(\hbar\omega) \cdot S_{\text{joint}} f_c (1-f_v)$$

$$r_{\text{stim}}(\hbar\omega) = B(\hbar\omega) \cdot S_{\text{joint}} (f_c - f_v)$$

isotropic, parabolic bands:

$$S_{\text{joint}} = \frac{4\pi}{k^3} (2m_j^*)^{3/2} (\hbar\omega - E_g)^{1/2}$$

$$\frac{1}{m_j} = \frac{1}{m_e} + \frac{1}{m_h}$$

2) no k -selection rule

$$r_{\text{spont}}(\hbar\omega) = \int B(E'_c) \cdot S_c(E'_c) \cdot S_v(E'_c - \hbar\omega) \cdot f_c(E'_c) \cdot (1 - f_v(E'_c - \hbar\omega)) \cdot dE'_c$$

$$r_{\text{stim}}(\hbar\omega) = \dots$$

$$S = \frac{4\pi}{e^2} M^{2/3} (2m_d^*)^{3/2} \cdot (E - E_g)^{1/2}$$

Theory of the Injection Laser

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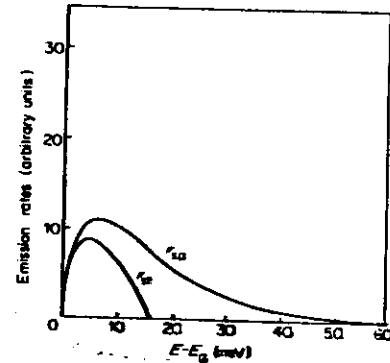


FIG. 2.4. Emission rates with k-selection rule calculated from eqns. (2.120) and (2.121)

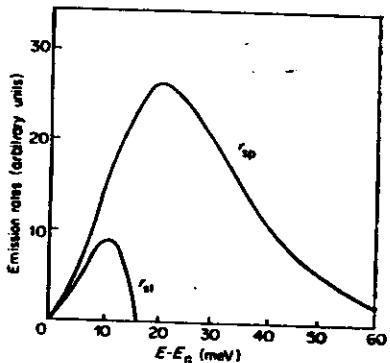
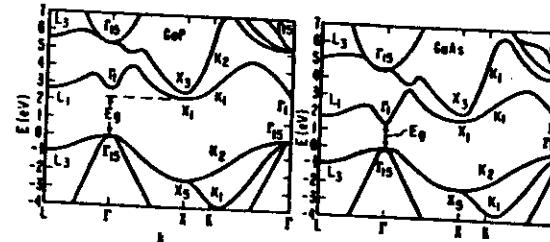


FIG. 2.5. Emission rates without k-selection rule calculated from eqns. (2.122) and (2.123)

1) III-V Compound Semiconductors

GaAs, GaAlAs, InP, GaInAsP, GaInAs
 Valenceband at T^* -point (degenerated)
 Conduction band at T^* (L, X)

2.) IV-VI Compound Semiconductors (Lead Salts)

PbS, PbTe, PbSe etc.

4 equivalent valence- and conduction band extrema at L-point

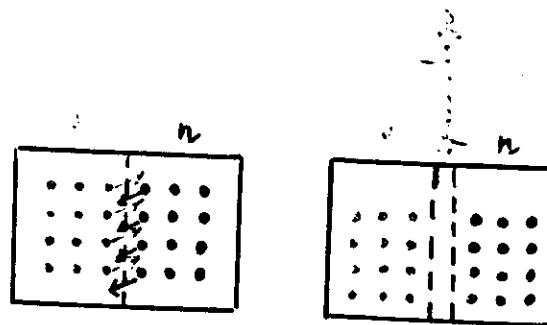
3.) Quantum Wells (2D free electron and holes)

GaAs/GaAlAs, GaInAsP/InP etc.

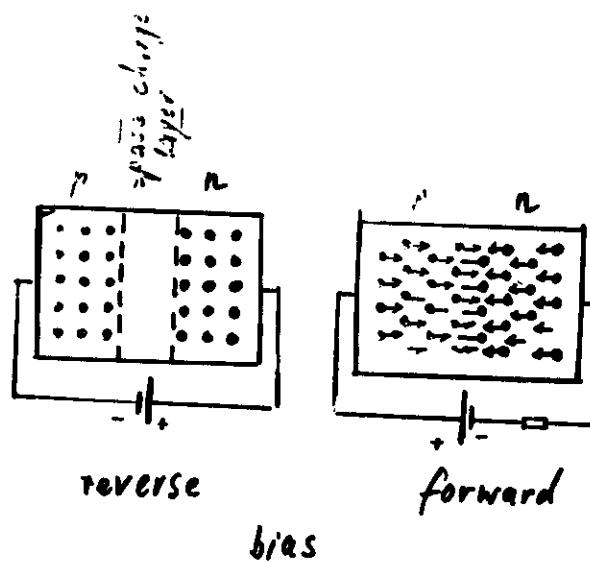
EXCITATION

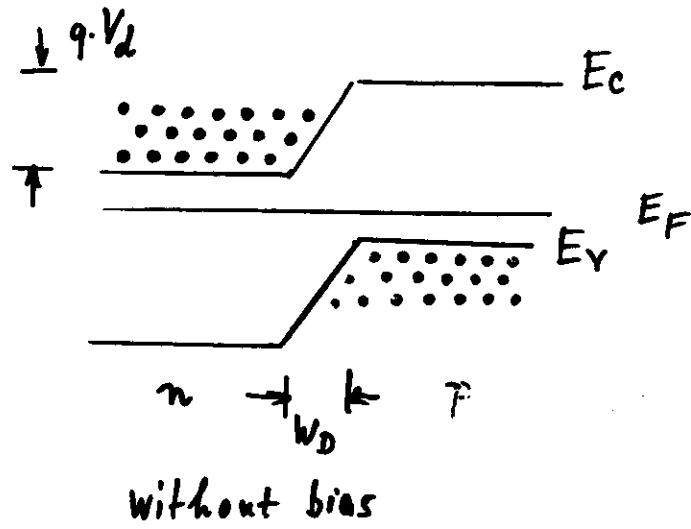
- Optical ($\hbar\omega > E_g$)
- electron beam
- electrical (p-n junction)
the heterodiode

p-n junction

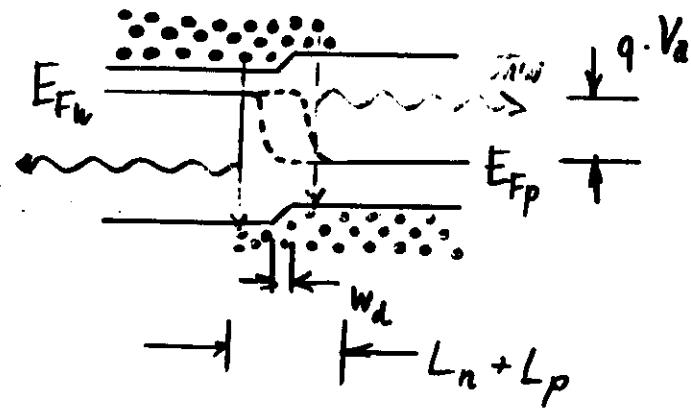
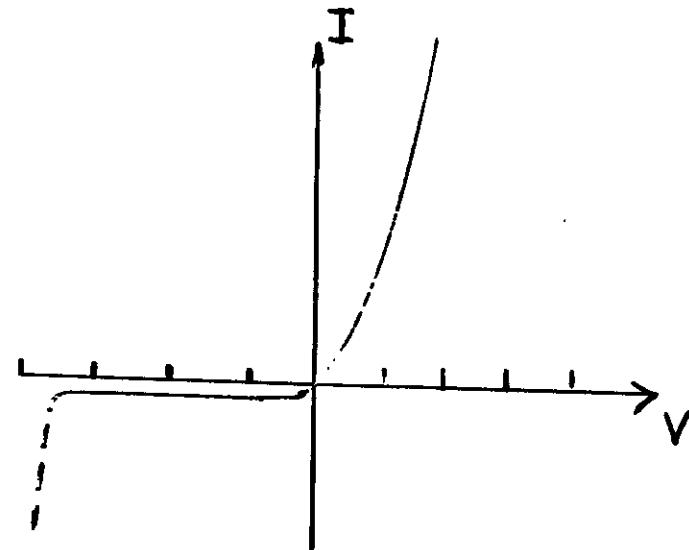


without voltage





I-V Characteristics

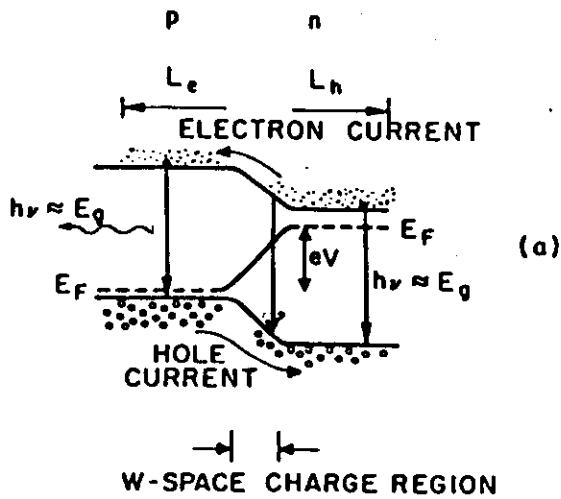


$$I = I_0 (e^{qV/nkT} - 1)$$

$$1 \leq n \leq 2$$

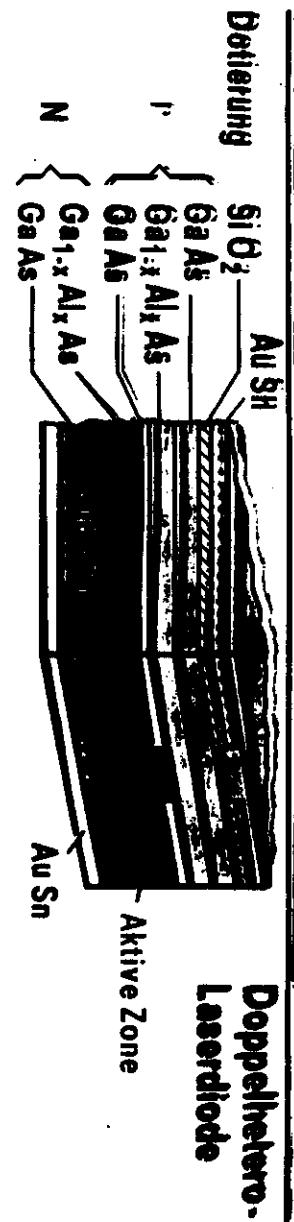
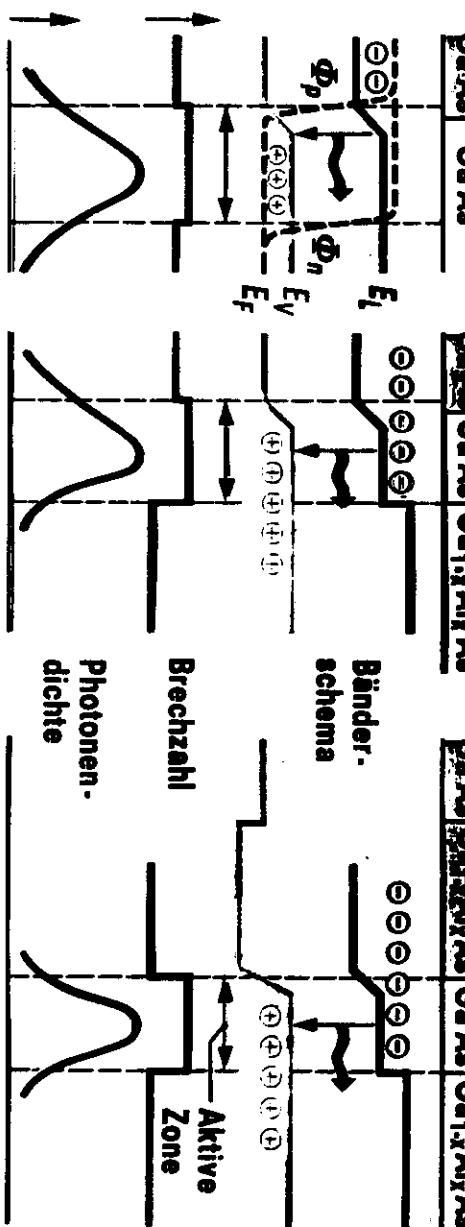
$n=1$ Diffusion Current

$n=2$ Recombination Current



Laserdiode

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**PN-Übergang****Einfachhetero-Übergang****Doppelhetero-Übergang**

Requirements for "Hetero-Materials"

- 1) larger band gap energy
- 2) lower refractive index
- 3) same lattice constant

Mixed compound semiconductors

- $\text{Al}_x\text{Ga}_{1-x}\text{As}$
- $\text{Ga}_x\text{In}_{1-x}\text{As}_y\text{P}_{1-y}$
- $\text{Pb}_{1-x}\text{Sn}_x\text{Te}$

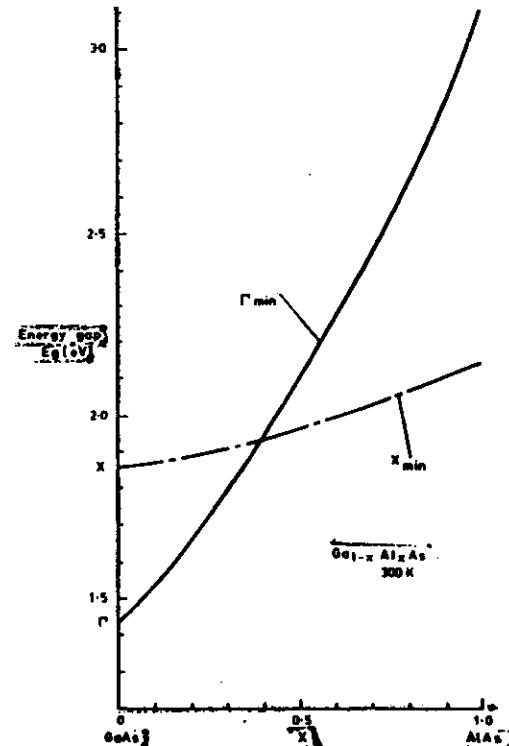


Figure 3.9 The direct and indirect energy gaps of $\text{Ga}_{1-x}\text{Al}_x\text{As}$ (after Casey and Panish¹¹)

GaInAsP Alloy Semiconductors

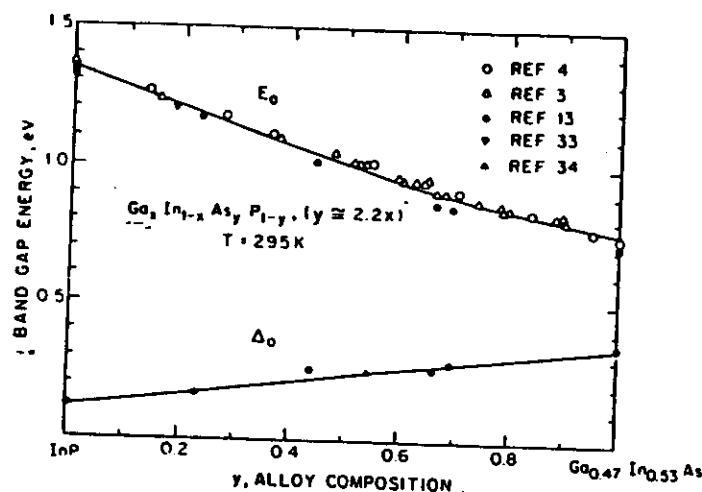


Figure 12.4 The energy gap (E_g) and spin-orbit splitting at the zone centre (Δ_0) in GaInAsP as function of alloy composition at 295 K. The full curves are calculated using the expressions given in the text and the disorder bowing shown in Figure 12.2. The measured data show very little scatter and are in excellent agreement with the theoretical curves

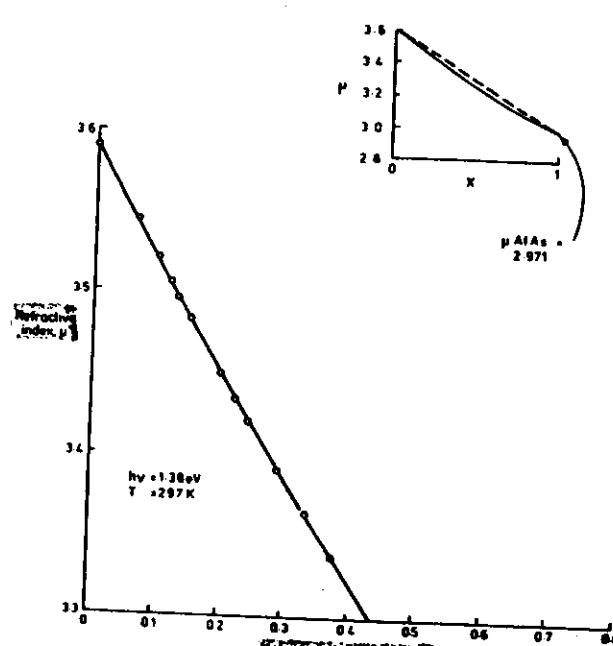


Figure 3.11 Refractive index of n-type $Ge_x In_{1-x} As_y P_{1-y}$ at $h\nu = 1.38$ eV as a function of composition x (after Casey *et al.*²²)

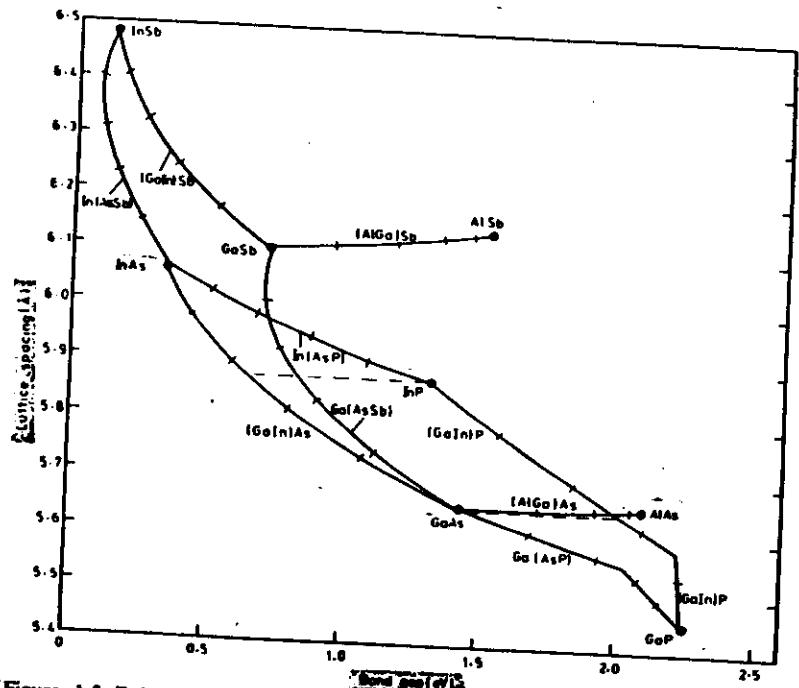


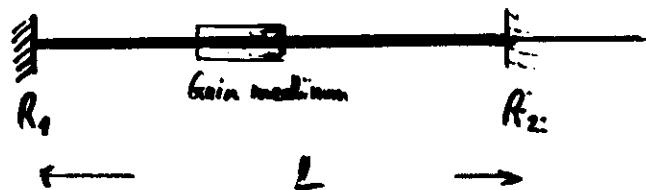
Figure 1.3 Relationship between band gap and lattice spacing in a number of mixed III/V semiconductors containing ternary combinations of Al, Ga, In and P.

LASER STRUCTURE

substrate materials : GaAs, InP, GaSb

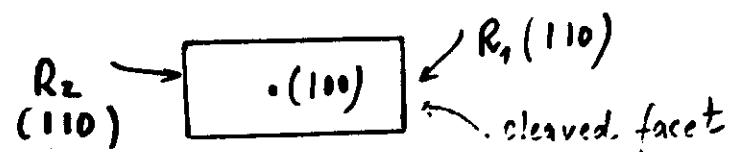
- GaAs / GaAlAs : o.k. ($x < 0.39$)
- InGaAsP / InP : o.k. ($In_{0.53}Ga_{0.47}As$)
- InGaAsSb / GaSb

Laser (conventional)



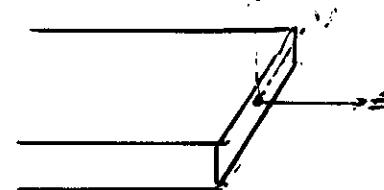
$$\text{lasing: } R_1 \cdot R_2 \exp[2(g-d)L] \geq 1$$

Semiconductor Laser:



	conv. laser	semicond. laser
R_1	100%	30%
R_2	95%	30%
$(g-d)$	$1 \dots 10 \text{ cm}^{-1}$	100 cm^{-1}
L	1m	$200 \mu\text{m}$

Modes:



longitudinal modes (z):

$$L = q \frac{\lambda}{2n^*(\lambda)} \Rightarrow \Delta\lambda = \frac{\lambda^2}{2L(\frac{\partial n^*}{\partial \lambda} - n^*)}$$

transversal modes (x, y):

$$[\nabla^2 + (n^* k)^2] \vec{E} = 0$$

$$n^* = n_1 - i n_2 = n(x, y)$$

$$\text{Ansatz: } n^{*2}(x, y) = n_0^{*2} \left[1 - \left(\frac{x}{x_0} \right)^2 - \left(\frac{y}{y_0} \right)^2 \right]$$

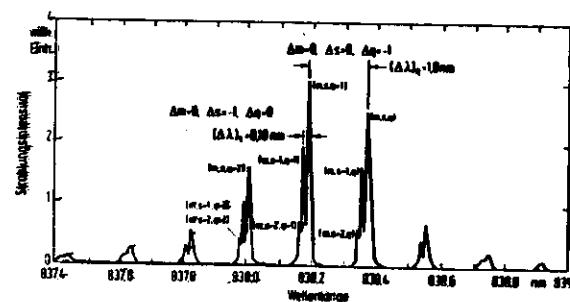
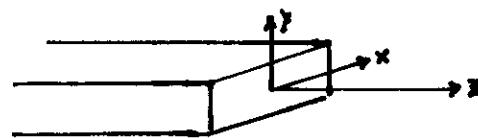
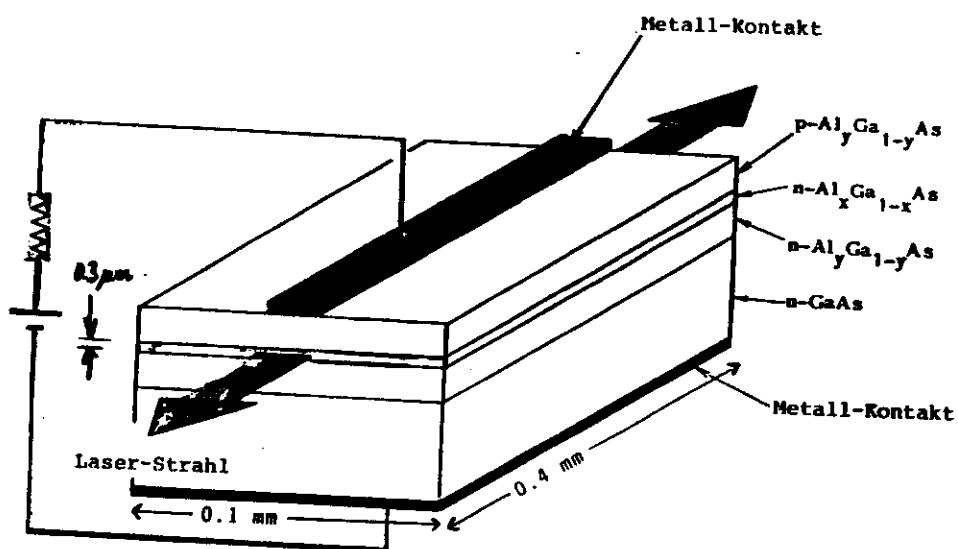


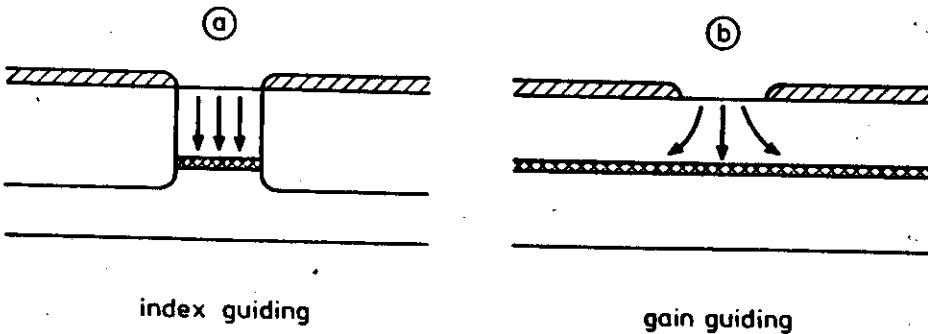
Abb. 8.16. Hochaufgelöstes Emissionspektrum einer GaAs-Laserdiode.
Man erkennt die axialen Grundmoden mit ihrem Abstand von 0,18 nm und
ihre Satelliten.

fundamental transverse mode
stabilization



x -direction: no problem ($d = 0.3 \mu\text{m}$)

- y -direction:
1. gain guiding (current)
 2. index guiding (refr. index)

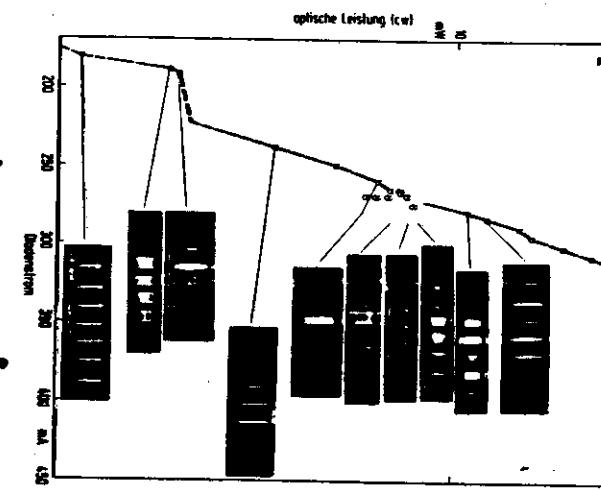


buried heterostructure
channeled substrate planar
metal clad ridge waveguide

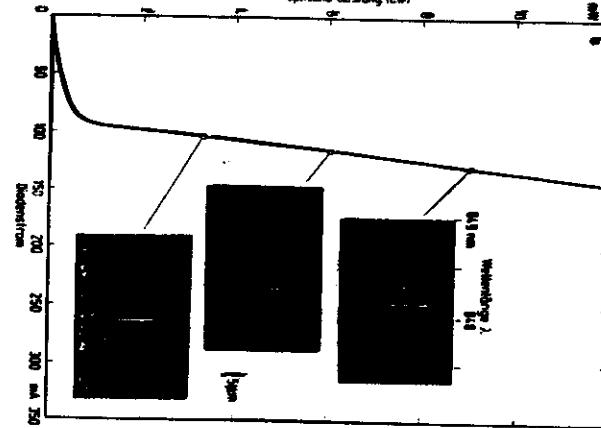
⋮

oxide stripe
V-groove
proton implanted

ohne laterales confinement



mit lateralem confinement



Index-Guided Laser

Burried-Heterostructure

BH-
(Hitachi)

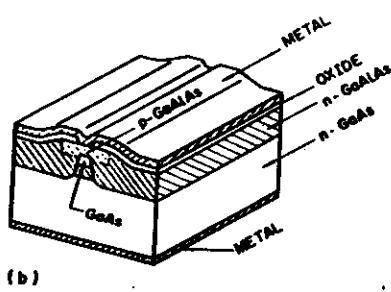
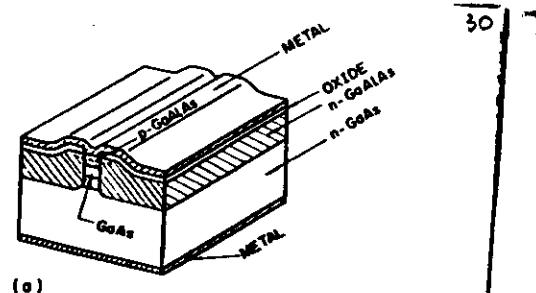


FIG. 1. Buried-heterostructure injection lasers. In both (a) type-I and (b) type-II lasers, the GaAs active regions are completely surrounded by GaAlAs. The lasers are typically 400 μm long, 300 μm wide, and 100 μm thick. The height of the raised area near the stripe region is about 1 μm or less. The drawings are not to scale in order to show the various regions clearly.

Channelled-Substrate Planar

CSP-
(Hitachi)

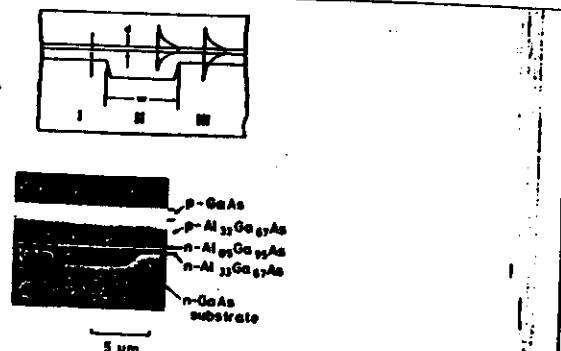
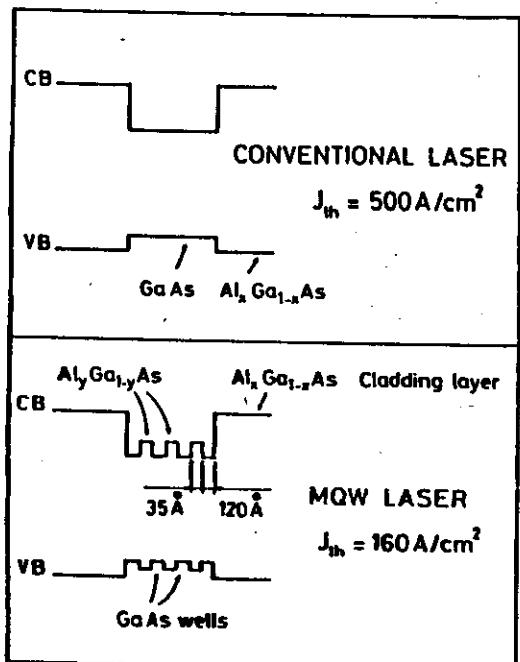


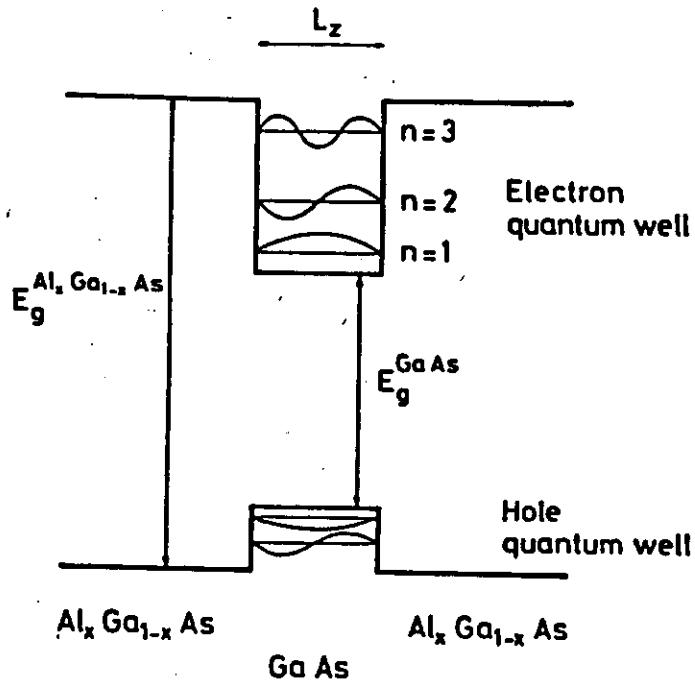
FIG. 1. Cross-sectional view of a channelled-substrate planar (CSP) laser perpendicular to the direction of light propagation (top), and a SEM photograph of the cleaved crystal face (bottom).

Quantum Well Lasers

- tunable band gap
- lower threshold ?
- less temperature sensitivity ?
- better noise performance ?



Schematic band diagram of a multiple quantum well laser (after Tsang [31]) with respect to conventional laser. Note the improvement in threshold current in MQW laser.



Quantum well in $\text{Al}_x\text{Ga}_{1-x}\text{As}/\text{GaAs}/\text{Al}_x\text{Ga}_{1-x}\text{As}$ double heterojunction: the lattice match between GaAs and $\text{Al}_x\text{Ga}_{1-x}\text{As}$ leads to a perfect quantum well

$$E = E_{||} + E_n$$

$$E_n = \frac{\hbar^2}{2m^*} \left(\frac{n \cdot \pi}{L_z} \right)^2$$

$$E_{||} = \frac{\hbar^2}{2m^*} (k_x^2 + k_y^2)$$

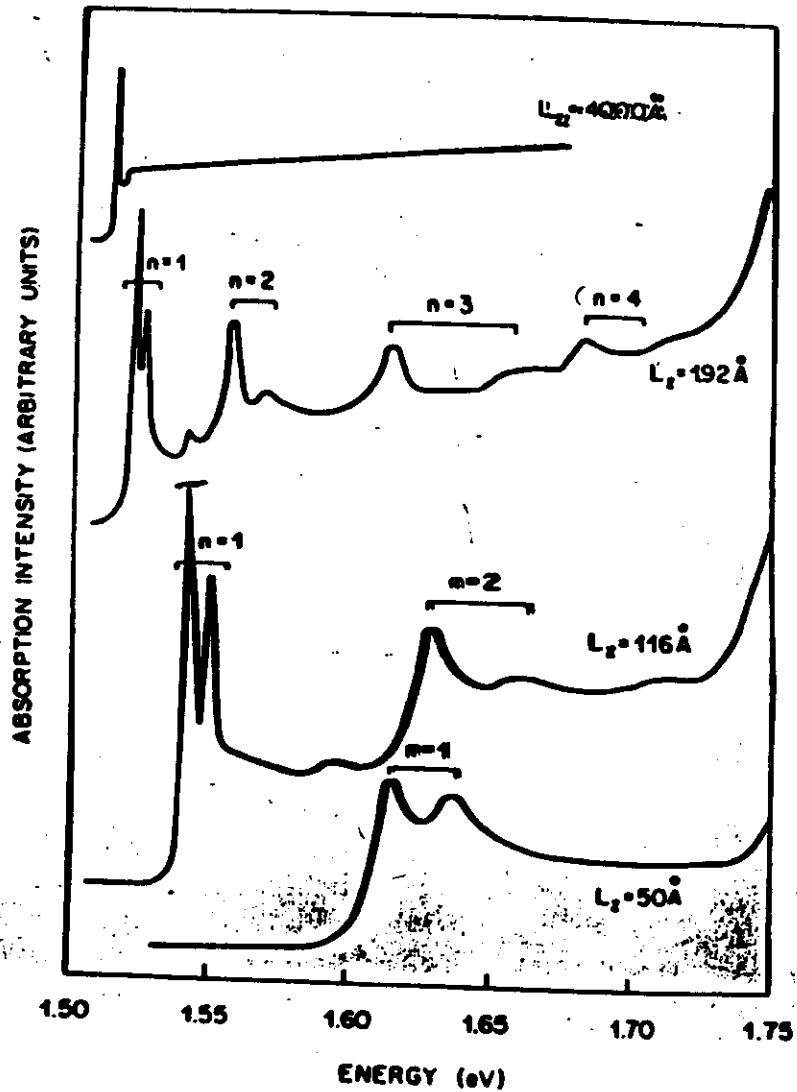
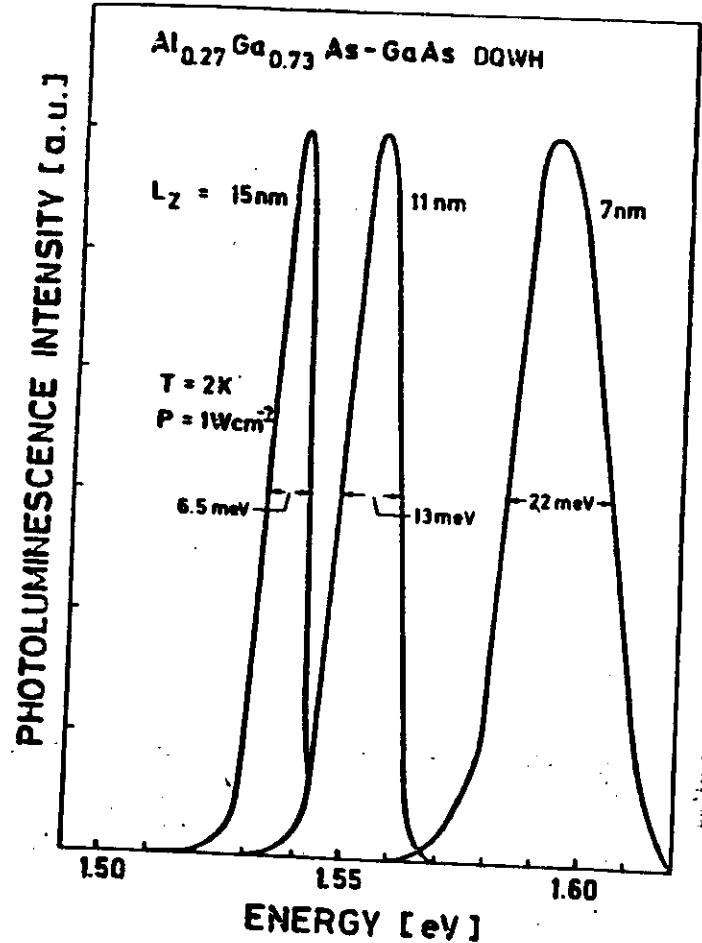


Fig. 7 Shift of photoluminescence of quantum wells with change of well width L_z (after ref. 32,25)

Gossard et al. 75

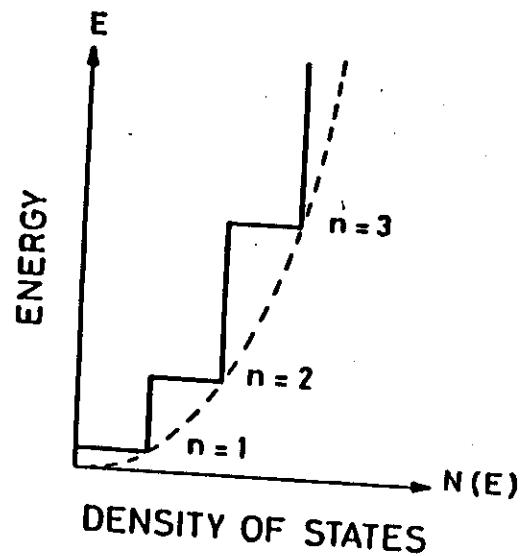
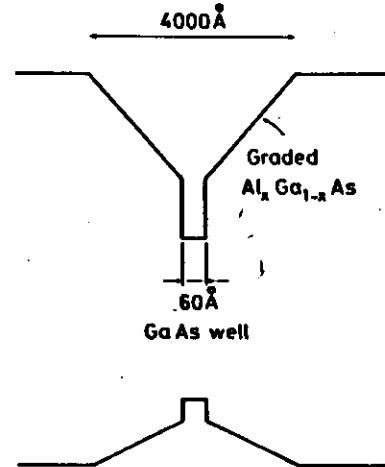


Fig. 7 Step-like density of states in a two-dimensional system

$$S(E) = \frac{W^*}{\pi h^2}$$

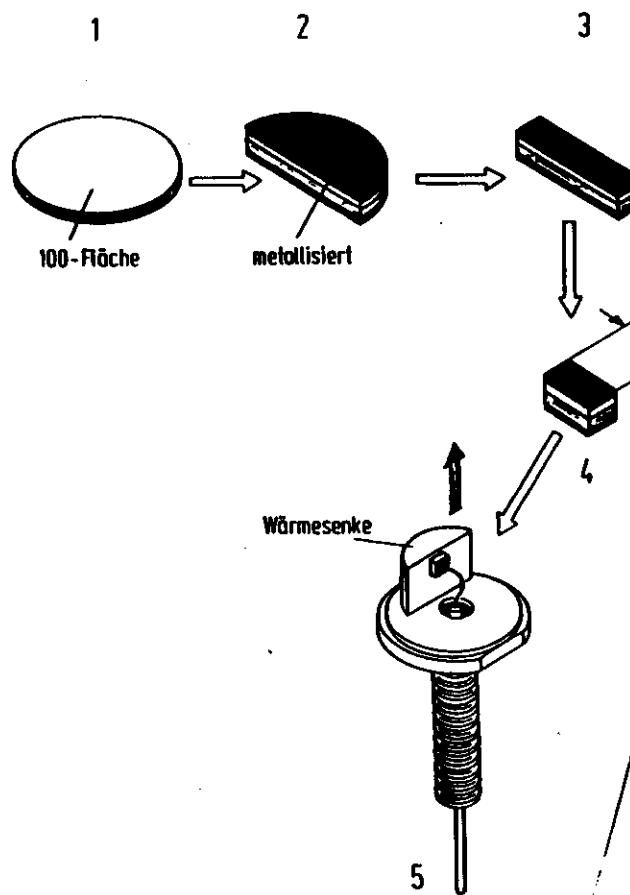


Schematic band diagram of a single-quantum laser positioned in a graded-refractive-index structure (after Hersee et al. [64]). QW lasers of this type present threshold current as low as 121 A/cm^2 .

Technology

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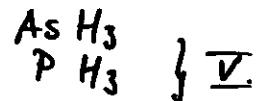
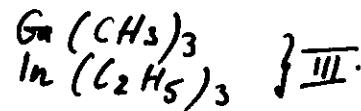


Technologies:

- Liquid Phase Epitaxy (LPE)
- Vapor Phase Epitaxy (VPE)

Chlorides: AsCl_3 , PCl_3
Hydrides: AsH_3 , PH_3

- Metal Organic Vapor Phase Epitaxy (MOCVD)



- Molecular Beam Epitaxy (MBE)

Applications:

- Data Storage (Optical Digital Audio Disc)
 GaAs , GaAlAs (visible lasers)
- Optical Communication (fibres)
short distance (buildings, cars, planes, ships, nuclear plants)
 $\text{GaAs}/\text{GaAlAs}$ (850 nm)
long distance, high bit rates: InGaAsP , InGaAs
(1.3 μm) (1.5 μm)
- Spectroscopy (IR) lead salt lasers
2 μm - 40 μm

{